Photoinitiated Polymerization-Induced Self-Assembly in the Presence of Surfactants Enables Membrane Protein Incorporation into Vesicles

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ABSTRACT

Photoinitiated polymerization-induced self-assembly (photo-PISA) is an efficient approach to predictably prepare polymeric nanostructures with a wide range of morphologies. Given that this process can be performed at high concentrations and under mild reaction conditions, it has the potential to have significant industrial scope. However, given that the majority of industrial (and more specifically biotechnological) formulations contain mixtures of polymers and surfactants, the effect of such surfactants on the PISA process is an important consideration. Thus to expand the scope of the methodology, the effect of small molecule surfactants on the PISA process, specifically for the preparation of unilamellar vesicles, was investigated. Similarly to aqueous photo-PISA findings in absence of surfactant molecules, the originally targeted vesicular morphology was retained in presence of varying concentrations of non-ionic surfactants, while a diverse set of lower-order morphologies was observed for ionic surfactants. Interestingly, a critical micelle concentration (CMC)-dependent behavior was detected in case of zwitterionic detergents. Additionally, tunable size and membrane thickness of vesicles were observed by using different types and concentration of surfactants. Based on these findings, a functional channel-forming membrane protein (OmpF porin), stabilized in aqueous media by surfactant molecules, was able to be directly inserted into the membrane of vesicles during photo-PISA. Our study demonstrates the potential of photo-PISA for the direct formation of protein-polymer complexes and highlights how this method could be used to design biomimicking polymer/surfactant nanoreactors.

INTRODUCTION

Small molecule surfactants, also known as surface-active agents, have been extensively utilized as wetting agents, emulsifiers, plasticizers, etc., in cleaning, food, oil, and textile industry.1,2 Self-assembled
amphiphilic polymer aggregates (macromolecular counterparts of surfactants) have also accumulated significant interest as they exhibit greater stability compared to surfactants, due to their superior mechanical and physical properties.\textsuperscript{3,4} Nowadays, mixed polymer-surfactant formulations that co-assemble at a certain critical aggregation concentration, are also used in various household, personal care and other industrial and biotechnological applications.\textsuperscript{5,6} Hence, the need to understand the effect of small molecule surfactants on polymeric assemblies and the interaction of such complex systems is increasingly required.

In an early report by Wesley \textit{et al.}, the interaction of anionic surfactant sodium dodecyl sulfate (SDS) with poly(2-(dimethylamino)ethyl methacrylate) (PDMAEMA) homopolymer chains was investigated.\textsuperscript{7} Small-angle neutron scattering revealed that the presence of polymer induced the micellization of the surfactant at concentrations below its CMC value, an observation also shown in a different study by Diamant and Andelman.\textsuperscript{8} Pata \textit{et al.} investigated the effect of non-ionic surfactant Triton\textsuperscript{TM} X-100 on poly(ethylene oxide)-b-poly(ethyl ethylene) and poly(ethylene oxide)-b-poly(butadiene) diblock copolymer vesicles.\textsuperscript{9} Higher resistance to membrane dissolution was achieved upon increasing the bilayer thickness of such vesicles. Armes and coworkers prepared epoxy-functional diblock copolymer vesicles by aqueous RAFT dispersion polymerization.\textsuperscript{10} Cross-linking of the membrane of the vesicles was achieved and the stability of vesicles towards externally added amounts of small molecule surfactants of different nature (\textit{i.e.} ionic and neutral) was then studied. The non-cross-linked vesicles could tolerate the presence of non-ionic surfactants, while they were easily disrupted upon exposure to ionic species (surfactant-induced dissociation). On the contrary, the cross-linked vesicles remained stable in presence of both non-ionic and ionic surfactants. More recently, Atanase \textit{et al.} studied the micellization behavior of poly(butadiene)-b-poly(2-vinylpyridine)-b-poly(ethylene oxide) (PB-b-P2VP-b-PEO) triblock copolymers as a function of pH and SDS concentration.\textsuperscript{11} SDS addition lead to a noticeable decrease of
particles’ size indicating the development of strong hydrophobic interactions between SDS and P2VP and the formation of surfactant-polymer complexes. Importantly, phospholipid/block copolymer hybrid vesicles (lipo-polymersomes) have been also studied in depth because of their similarity, in terms of thickness and hydrophobicity, to cell membranes and their advantages of combining the best features of both species.\textsuperscript{12-15}

Over recent years, polymerization-induced self-assembly (PISA) has become a widely-utilized and efficient synthetic methodology to produce block copolymer nano-objects of controlled size, morphology and tunable properties.\textsuperscript{16,17} Owing to the fact that traditional block copolymer self-assembly methods are mostly conducted at low polymer concentrations ($\leq 1\%$ w/w) and in almost all cases require further post-polymerization processing, which makes it difficult to implement on a large scale, PISA has become an alternative one-pot route to reproducibly prepare nano-objects at high concentrations (10-50\% w/w).\textsuperscript{18,19} Controlled radical polymerization techniques such as nitroxide-mediated polymerization (NMP),\textsuperscript{20} atom-transfer radical polymerization (ATRP),\textsuperscript{21} and reversible addition-fragmentation chain-transfer (RAFT) polymerization\textsuperscript{22-25} have been mainly applied in this process, although RAFT polymerization is still the most popular method owing to its high versatility and broad applicability. Typically, in RAFT-mediated dispersion PISA, a solvophilic macromolecular-chain transfer agent (macro-CTA) is chain-extended using miscible monomers such that the growing second block gradually becomes insoluble, which drives \textit{in situ} self-assembly to form amphiphilic diblock copolymers. These generate a set of higher-order polymeric nanostructures with morphologies that evolve by varying the degree of polymerization (DP) and solids concentration.\textsuperscript{26}

Nevertheless, research towards bio-related or stimuli-responsive nanomaterials produced by aqueous PISA is currently limited. This is mainly attributed to the elevated reaction temperatures required for most thermally initiated aqueous PISA formulations that can lead to denaturation of delicate biomolecules such
as proteins, enzymes or antibodies. Recently, an increasing number of studies based on aqueous visible light-initiated PISA (photo-PISA) at ambient temperatures has been reported, showing great promise in the design and preparation of novel materials of particular biotechnological and biomedical interest.

The design of facile and mild routes for the preparation of well-defined single-phase vesicles by photo-PISA is of great interest as it allows for the development of cargo-loaded nanocarriers, in a single step, which is especially important for the encapsulation of delicate biomolecules. To date, several studies on the encapsulation of hydrophilic proteins and enzymes inside polymeric vesicles via one-pot aqueous photo-PISA under mild reaction conditions (i.e. low temperature, visible light and aqueous media) have been reported. On the contrary, conventional methods used for the insertion of hydrophobic and/or amphiphilic (macro)molecules (e.g. drugs, enzymes, receptors, and membrane proteins) into vesicles are not often appropriate for delicate and very hydrophobic biomolecules. Indeed, for very hydrophobic biomolecules (e.g. membrane proteins), such uptake into vesicles cannot be achieved without the presence of solubilizing agents such as surfactants. The incorporation of membrane proteins (specifically channel proteins, such as OmpF) into vesicles has been pioneered by Meier, Palivan and coworkers who have demonstrated such nanoconstructs as synthetic cell mimics (organelles). To further broaden the scope of the synthesis of such membrane protein-vesicle complexes we were interested in exploring photo-PISA to allow for uptake into the hydrophobic domain formed during polymerization (given its mild, tolerant and scalable conditions).

To achieve this, we first explored the interaction and effect of small molecule surfactants of different critical micelle concentration (CMC) values and nature (i.e. neutral, ionic and zwitterionic), commonly used in various biotechnological applications, on the self-assembly process of a poly(ethylene glycol)-b-poly(2-hydroxypropyl methacrylate) (PEG-b-PHPMA) block copolymer system developed by aqueous photo-PISA, while always targeting unilamellar vesicles (ULVs) as the desired final morphology. We
were able to demonstrate that mixed block copolymer/surfactant vesicles with tunable size and membrane thickness could be obtained upon appropriate usage of different types and concentration of surfactants. Based on these findings, we then moved towards using these conditions for incorporation of the pore-forming outer membrane protein F (OmpF), which is insoluble in water and requires the addition of surfactants for solubilization, hence is challenging to incorporate directly into polymeric self-assemblies. This was achieved by conducting photo-PISA in the presence of OmpF, which was first stabilized by a non-ionic surfactant, to allow for direct reconstitution into the membrane of the vesicles, as demonstrated by their enhanced permeability. We propose that this demonstration highlights the potential application of photo-PISA methodology, in presence of surfactants, for insertion of challenging hydrophobes and hence could contribute significantly to the further development of biomembrane-mimicking nanoreactors.
RESULTS AND DISCUSSION

Based on findings from other related literature reports by Armes and Zhang’s groups, and more recently by our group for similar PISA systems, a poly(ethylene glycol) macro-chain transfer agent with same molecular weight (5.0 × 10^3 g mol⁻¹, DP = 113) as the one used in these studies was first synthesized. This was achieved through esterification of an acid functionalized chain transfer agent (CEPA CTA) with a poly(ethylene glycol) monomethyl ether homopolymer (PEG_{113}-OH) by DCC coupling chemistry (esterification efficiency = 93%, See Supporting Information for experimental details).

This water-soluble macro-CTA was then chain-extended under dispersion polymerization conditions using a water-miscible monomer, 2-hydroxypropyl methacrylate (HPMA), as the core-forming block. It should be noted that the monomer was a mixture of two isomers 2-hydroxypropyl methacrylate (major, 75% mol) and 2-hydroxyisopropyl methacrylate (minor, 25% mol). Aqueous RAFT-mediated photo-PISA of HPMA occurred upon 405 nm visible-light irradiation of the solution at 37 °C under N₂ atmosphere for the synthesis of PEG-b-PHPMA nano-objects (Scheme S1) and complete monomer conversion (> 99%) was achieved after 2 hours of reaction, as determined by ¹H-NMR spectroscopy (Figure S1). It should be mentioned that the polymerization process was promoted in the absence of an initiator or catalyst, following the well-documented “photoiniferter” mechanism.

Based on the morphologies diagram for photo-PISA of PEG_{113}-b-PHPMA in deionized (DI) water recently reported by our group, well-defined unilamellar vesicles (ULVs) were formed when targeting DP_{HPMA} = 400 at 10 wt% HPMA (11 wt% solids content) (Scheme 1A). SEC analysis in DMF of a lyophilized PEG_{113}-b-PHPMA_{400} sample confirmed the successful chain-extension of HPMA and revealed the controlled character of the photo-PISA process as indicated by the relatively narrow molecular weight distribution determined (M_{n,SECRI} = 80.1 × 10^3 g mol⁻¹, D_{M,RI} = 1.25) (Table S1).
Scheme 1. (A) Schematic illustration showing the obtained PEG\textsubscript{113}-b-PHPMA\textsubscript{400} nano-object morphologies after photo-PISA in deionized water and in different type surfactant solutions at concentrations equal to or higher than the critical micelle concentration (CMC) of each surfactant. (B) Summary of chemical structures and main characteristics of the surfactants used in the present study (CMC values in water as reported in literature).

Dry-state stained TEM imaging revealed the successful formation of ULVs of uniform size, while DLS analysis also confirmed a unimodal particle size distribution with hydrodynamic diameter ($D_h$) in the range of 350-400 nm (Figure S2). The shape, size and unilamellar character of the developed PEG\textsubscript{113}-b-PHPMA\textsubscript{400} vesicles in solution were confirmed by cryo-TEM imaging, while their average membrane thickness was also determined, as 26.8 ± 3.4 nm (Figure S3). These findings were in good agreement with our previously reported characterization results for the same system, suggesting the facile reproducibility.
of the photo-PISA process. Zeta potential measurements of the prepared vesicles after purification in DI water showed a negative value of -30.5 ± 0.4 mV, mainly attributed to the free –OH groups of the relatively hydrated PHPMA membrane that are not entirely screened by the PEG 5kDa chains. It is also important to mention that the purification process of the particles by centrifugation/resuspension cycles in DI water didn’t significantly affect any of their characteristics (i.e. shape, size and zeta potential).

The key aim of this research was to evaluate the impact of small molecule surfactants (detergents) used in various industrial and biotechnological applications, such as solubilizing agents of hydrophobic membrane proteins, on the formulations obtained by photo-PISA. Aqueous photo-PISA reactions for the development of PEG\(_{113}\)-b-PHPMA\(_{400}\) nano-objects were carried out in presence of various surfactants (non-ionic, anionic, cationic and zwitterionic) with differing CMC values, under the same polymerization conditions described above (Scheme 1). A low-CMC non-ionic surfactant with a hydrophilic oligo(ethylene glycol) head, Triton™ X-100 (n = 9-10), and two non-ionic pyranoside surfactants, \(n\)-dodecyl \(\beta\)-\(D\)-maltoside (DDM, low-CMC) and octyl \(\beta\)-\(D\)-glucopyranoside (OG, high-CMC), were first studied. Additionally, a model anionic surfactant, sodium dodecyl sulfate (SDS), and a cationic surfactant, cetyltrimethylammonium bromide (CTAB), were also investigated. Notably, the effect of two zwitterionic surfactants, 3-[(3-cholamidopropyl)dimethylammonio]-1-propanesulfonate (CHAPS, high-CMC) and \(n\)-dodecylphosphocholine (DPC, low-CMC) on photo-PISA nano-object morphologies was finally assessed. It is worth mentioning that the presence of 10 wt% HPMA in PISA solutions didn’t significantly alter the CMC value of surfactants, as determined by surface tension analysis (Figure S4). The developed polymer-surfactant hybrid formulations could potentially be utilized for \textit{in-situ} incorporation of unstable in aqueous media functional (macro)molecules, such as receptors, peptides, enzymes, membrane proteins and DNA, and fabrication of biomimetic nanoreactors. The observed PEG\(_{113}\)-b-PHPMA\(_{400}\) diblock copolymer/surfactant morphologies formed by aqueous photo-PISA are schematically summarized in
Scheme 1A, while the chemical structures along with the main characteristics of the surfactants used in the present study are shown in Scheme 1B.

In all cases, photo-PISA reactions were carried out at three different concentrations of each individual surfactant (i.e. at concentrations equal to each detergent’s CMC and also at 10 times lower and 10 times higher concentration levels) for the synthesis of nano-objects for the same block copolymer. Moreover, in cases of non-ionic surfactants Triton™ X-100 and DDM, and zwitterionic CHAPS and DPC additional surfactant concentrations were also investigated, due to the wide use of these particular surfactants in numerous biotechnologically relevant applications. Purification of samples was achieved by consecutive centrifugation/resuspension cycles in DI water for the removal of unreacted monomer and excess of non-incorporated surfactant molecules. ¹H-NMR spectroscopy was used for determination of surfactant incorporation in purified OG and CHAPS samples at 10×CMC (high-CMC surfactants with visible peaks) (Figure S5). For OG, a surfactant incorporation of 6% was calculated, while a higher surfactant incorporation of 14.5% was calculated in the case of CHAPS.

**Molecular characteristics of polymer-surfactant photo-PISA formulations.** The final monomer conversion after photo-PISA in different surfactant solutions for the synthesis of PEG₁₁₃-b-PHPMA₄₀₀ nano-objects was first determined by ¹H-NMR spectroscopy. It was found that the reaction times of photo-PISA processes were not significantly affected by the presence of surfactants in the system, with almost quantitative monomer conversions (≥ 96%) achieved after 2 h of irradiation time in almost all cases (Table S2). The only exception was noticed at [CHAPS] = 160.0 mM (= 20×CMC), where monomer conversion of 70% was calculated (polymerization repeated in duplicate). This rate retardation could be explained by the inability of monomer to reach the gradually growing copolymer chains due to their high solubilization inside the core of the surfactant micelles at high CHAPS concentration. Repeating the polymerization procedure in the same CHAPS solution for 18h, resulted in > 99% conversion. SEC analyses in DMF of
purified and lyophilized PEG_{113}-b-PHPMA_{400} samples at surfactant concentrations \((C_{\text{surf}})\) equal to CMC proved the relatively controlled character of polymerization in each case (Figure 1). In particular, a minimal \(M_n\) increase was observed in almost every polymer/surfactant sample as compared to PEG_{113}-b-PHPMA_{400} diblock copolymers formed in DI water, accompanied by a minor \(D_M\) increase from 1.25 (DI water) to 1.29-1.33 (surfactant solutions). Notably, no major \(M_n\) and \(D_M\) differences were detected between diblock copolymer samples in surfactant species of different nature. SEC eluograms of selected diblock copolymer samples prepared at \(C_{\text{surf}} > \text{CMC}\) revealed that a 10-fold surfactant concentration increase didn’t result in a further increase of molecular weight and \(D_M\) values (Figure S6). These findings indicate that the presence of surfactants during photo-PISA didn’t markedly affect the molecular characteristics of the developed PEG_{113}-b-PHPMA_{400} diblock copolymers and reveal the high tolerance of dispersion polymerization process toward different types of surfactants.
Figure 1. Representative SEC RI traces for PEG$_{113}$-b-PHPMA$_{400}$ diblock copolymers synthesized in presence of (A) non-ionic, (B) ionic and (C) zwitterionic surfactants at $C_{\text{surf.}} = \text{CMC}$ in each case, along
with their corresponding $M_n$ (g mol$^{-1}$) and $D_M$ values calculated from PMMA standards, using 5 mM NH$_4$BF$_4$ in DMF as the eluent.

Based on the SEC results, it can be assumed that all nano-objects’ size variations and morphology transitions observed are attributed to the nature and CMC value (i.e. amount) of the surfactant used in each case and not to loss of polymerization control during photo-PISA in different surfactant solutions. Exhaustive DLS analysis of the received PEG$_{113}$-b-PHPMA$_{400}$ photo-PISA formulations before and after purification process was performed to monitor the hydrodynamic diameter ($D_h$) and polydispersity (PD) changes upon increasing concentration of surfactants. Dry-state stained TEM imaging was used for the observation of the prepared polymer-surfactant nano-object morphologies in each case, while the received purified hybrid nano-objects in solution, formed by photo-PISA at $C_{surf.} = $ CMC, were also characterized by cryogenic transmission electron microscopy (cryo-TEM). Additionally, in case of vesicles, the average membrane thickness was calculated from statistical analysis by measuring at least 150 particle membranes in each sample.

**Photo-PISA nano-objects developed in presence of non-ionic surfactants.** In case of non-ionic and low-CMC surfactant Triton™ X-100, it is evident that $D_h$ and PD values were found to be similar to those of original PEG$_{113}$-b-PHPMA$_{400}$ vesicles in DI water, remaining constant for a wide range of surfactant concentrations (Figure 2A-I). Near-identical behavior was noticed for DDM, which is also another low-CMC non-ionic detergent with almost equal CMC value to Triton™ X-100 (Figure 2B-I). It should also be noted that in these cases the purification process did not affect the $D_h$ or PD values, showing that the nanostructures remain intact after centrifugation/resuspension in DI water. From dry-state TEM imaging, it was observed that spherical unilamellar vesicles (ULVs) of uniform size (350 nm – 400 nm) were developed in both cases, analogous to those formed in DI water (Figures S7-S10). Results from cryo-TEM
analysis were in good agreement with those received from other characterization methods. It is apparent that ULVs of comparable size and membrane thickness to PEG$_{113}$-b-PHPMA$_{400}$ vesicles in DI water were formed in cases of non-ionic Triton™ X-100 and DDM, at $C_{surf.} = \text{CMC}$ (Figures 2A-II, 2A-III, 2B-II and 2B-III). As a matter of fact, membranes were found to be slightly thicker in both samples (average membrane thickness $= 27 \text{ nm} – 29 \text{ nm}$) compared to those in DI water, suggesting the limited insertion of surfactant molecules in the particles’ hydrophobic bilayer leading to a negligible increase of average membrane thickness. On the contrary, in case of high-CMC non-ionic surfactant OG, a significant particles’ size increase from 350 nm to 760 nm was noticed at surfactant concentrations equal to or 10 times higher than its CMC value. In this case, the measured PD values were also found to be higher than those in the other non-ionic surfactants, ranging from 0.1 to 0.2, indicating the formation of particles with broader size distribution (Figure 2C-I). Dry-state TEM imaging at [OG] = 18.0 mM (= CMC) confirmed the formation of giant unilamellar vesicles (GULVs) of varying sizes, while TEM images at [OG] = 180.0 mM (= 10×CMC) revealed the co-existence of GULVs along with a population of large multilamellar vesicles (MLVs) (Figures S11 and S12). As determined by cryo-TEM imaging, exceptionally large ULVs with rough outline, significantly thicker membranes (average membrane thickness $\approx 40 \text{ nm}$) and broad bilayer thickness distribution were formed in case of exceedingly high-CMC OG, at $C_{surf.} = \text{CMC}$ (Figure 2C-II and 2C-III). These findings suggest that the higher surfactant weight fraction required for the preparation of OG solutions leads to the formation of larger hybrid polymer-surfactant vesicular structures, due to stronger interaction between OG molecules and vesicle membranes that aids chain mobility and exchange, thereby allowing larger vesicles to form. However, the significantly lower relative amount of surfactant needed for the preparation of Triton™ X-100 and DDM solutions is not able to strongly affect the size or the interfacial curvature of PEG$_{113}$-b-PHPMA$_{400}$ vesicles. The evidently high tolerance of photo-PISA toward non-ionic surfactant species is also in agreement with relevant literature.
reports on polymer/surfactant assemblies, supporting that there is no or limited interaction between non-ionic small molecule surfactants and neutral polymer structures.\textsuperscript{8,10}

Figure 2. Summary of DLS and cryo-TEM analyses results for PEG\textsubscript{113}-b-PHPMA\textsubscript{400} diblock copolymer nano-objects developed by aqueous photo-PISA in presence of non-ionic surfactants Triton\textsuperscript{TM} X-100 (A), DDM (B) and OG (C). For each individual surfactant: (I) DLS of crude and purified formulations for the
monitoring of $D_h$ and PD changes upon increasing surfactant concentration (the error shows the standard deviation from 5 repeat measurements, while the dashed line indicates the CMC value of each detergent). (II) Representative cryo-TEM images of purified PEG$_{113}$-$b$-PHPMA$_{400}$ nano-objects formed at $C_{surf.} =$ CMC. (III) Distribution of vesicles’ membrane thicknesses measured from statistical analysis and calculated average membrane thickness (the error shows the standard deviation from at least 150 particle membranes).

**Photo-PISA nano-objects developed in presence of ionic surfactants.** In the case of commonly used high-CMC anionic surfactant SDS, DLS measurements showed significant size and PD differences and co-existence of mixed populations for the developed nano-objects upon increasing detergent concentration (Figures 3A-I and 4A-I). The corresponding hydrodynamic diameter of particles was similar to that of vesicles in DI water only at [SDS] = 0.82 mM (≈ 0.1×CMC), while the observed variations of $D_h$ and PD values at [SDS] ≥ CMC indicate strong surfactant interaction with the copolymer chains and the occurrence of morphological transitions. In particular, dry-state TEM imaging verified the development of spherical ULVs around 350 nm – 420 nm at low SDS concentration (Figures 4A-II and S13). In contrast, photo-PISA at [SDS] = 8.2 mM (≈ CMC) resulted in the formation of mixed morphologies of spherical micelles, short worms and ULVs of various sizes, as judged by dry-state and cryo-TEM imaging, due to greater interaction of surfactant molecules with the block copolymer chains leading to interfacial curvature changes (Figures 3A-II, 4A-II and S14). In this case, the average membrane thickness of vesicles was calculated to be around 45 nm and was remarkably higher compared to that of vesicles in DI water (Figure 3A-III). A 10-fold surfactant concentration increase to [SDS] = 82.0 mM further promoted the surfactant-induced dissociation of polymer/surfactant assemblies towards lower-order structures. Dry-state TEM imaging showed a significant increase in the worm-like and spherical micelles’ population against ULVs (Figures 4A-II and S15). In addition to the described results, the well-known ability of SDS to denature
enzymes and other proteins makes it unsuitable candidate for enzyme-loaded nanoreactor development and amphiphile incorporation applications. On the other hand, for cationic surfactant CTAB, a direct vesicle-to-sphere morphology transition was observed at concentrations [CTAB] ≥ CMC, as judged by DLS and dry-state TEM analyses. DLS measurements of crude and purified samples for removal of unbound detergent, revealed a significant $D_h$ decrease from 400 nm to 250 nm upon increasing CTAB concentration, while PD values were constantly in the range of 0.15 – 0.2 (Figure 3B-I). DLS size distributions showed the presence of two particle populations for small spherical micelles and vesicles at [CTAB] ≥ 0.8 mM, while a single population of vesicles was detected at low CTAB concentration (Figure 4B-I). DLS results were also verified by dry-state TEM imaging of purified samples at different surfactant concentrations. Unilamellar vesicles identical to those formed in DI water were solely observed at [CTAB] = 0.08 mM (= 0.1×CMC) (Figures 4B-II and S16), while the formation of spheres, small and large ULVs was revealed at [CTAB] = CMC (Figures 4B-II and S17). Cryo-TEM imaging at this CTAB concentration also confirmed the co-existence of a mixture of very small and larger ULVs, while an average bilayer thickness of around 28 nm, similar to that of low-CMC non-ionic surfactant samples, was measured from digital image analysis (Figures 3B-II and 3B-III). A further increase of [CTAB] from 0.8 to 8.0 mM (= 10×CMC) favored the formation of spherical micelles, hence the population of spheres was notably larger than that of vesicles in this case (Figures 4B-II and S18). This could be explained by the gradual introduction of positive charges, caused by the increasing [CTAB], that blend into the diblock copolymer chains developing strong repulsive forces and leading to dissociation of vesicles in favor of spheres (i.e. significant increase of interfacial curvature). It should also be mentioned that complete charge screening occurred at [CTAB] = 8.0 mM (measured zeta potential = -1.25 ± 0.32 mV), owing to neutralization of the negative vesicles’ charge by the positively charged surfactant molecules. For both ionic surfactants, comparable findings were also discussed by Armes’ group in a previous study and are mainly attributed
to the high sensitivity of RAFT-mediated PISA to the presence of ionic molecules, which makes it more difficult to obtain higher-order morphologies in contrast to the less-disruptive non-ionic surfactants.\textsuperscript{10,52}

The greater disruptive power of anionic surfactant SDS as compared to that of cationic CTAB is mainly attributed to the greater molar concentration for a given mass concentration of the former (\textit{i.e.} $\text{CMC}_{\text{SDS}} > \text{CMC}_{\text{CTAB}}$).\textsuperscript{10}
Figure 3. Summary of DLS and cryo-TEM analyses results for PEG$_{113}$-b-PHPMA$_{400}$ diblock copolymer nano-objects prepared by aqueous photo-PISA in presence of ionic surfactants SDS (anionic) (A) and CTAB (cationic) (B), and zwitterionic surfactants CHAPS (C) and DPC (D). For each individual surfactant: (I) DLS of crude and purified formulations for the monitoring of $D_h$ and PD changes upon increasing surfactant concentration (the error shows the standard deviation from 5 repeat measurements, while the dashed line indicates the CMC value of each detergent). (II) Representative cryo-TEM images of purified PEG$_{113}$-b-PHPMA$_{400}$ nano-objects formed at $C_{surf.} = \text{CMC}$. (III) Distribution of vesicles’ membrane thicknesses measured from statistical analysis and calculated average membrane thickness (the error shows the standard deviation from at least 150 particle membranes).
**Figure 4.** DLS analyses and dry-state TEM imaging results for PEG\textsubscript{113}-b-PHPMA\textsubscript{400} diblock copolymer nano-objects developed by photo-PISA in aqueous solutions of anionic surfactant SDS (A) and cationic surfactant CTAB (B), upon gradually increasing \(C_{\text{surf}}\). For each individual surfactant: (I) Intensity-weighted size distributions of purified PEG\textsubscript{113}-b-PHPMA\textsubscript{400} nano-objects developed in detergent solutions of different concentrations, as determined by DLS. (II) Representative dry-state TEM micrographs of purified PEG\textsubscript{113}-b-PHPMA\textsubscript{400} nano-objects formed in presence of ionic surfactants, stained with 1 wt\% UA, revealing a transition from vesicles (V) to mixed morphologies (S + W + V) upon increasing [SDS] and a direct vesicle-to-sphere morphology transition upon increasing [CTAB].

**Photo-PISA nano-objects developed in presence of zwitterionic surfactants.** Importantly, the effect of two model zwitterionic (ampholytic) surfactants on PEG\textsubscript{113}-b-PHPMA\textsubscript{400} photo-PISA nano-object formulations was thoroughly investigated. In the case of high-CMC steroid surfactant CHAPS, slight size
differences were observed at low surfactant concentrations (i.e. [CHAPS] ≤ CMC), as judged by DLS (Figure 3C-I). However, a dramatic $D_h$ decrease from 420 nm to 110 nm was observed at [CHAPS] = 80.0 mM (=10×CMC) (PD = 0.18, zeta potential = -15.6 ± 0.3 mV), while further [CHAPS] increase to 160.0 mM (= 20×CMC) resulted in a notable $D_h$ decrease to almost 50 nm (PD = 0.04, zeta potential = -10.4 ± 1.9 mV), indicating the occurrence of morphological transitions from ULVs to lower-order structures upon increasing detergent concentration. Interestingly, dry-state TEM imaging revealed a morphologically distinct vesicle-to-worm-to-sphere transition upon increasing [CHAPS] from CMC to 10×CMC and subsequently to 20×CMC (Figures 5A and S19-S21). ULVs of uniform shape and size with significantly thicker hydrophobic membranes (average membrane thickness ≈ 38 nm) and rough outline were formed at [CHAPS] = 8.0 mM (= CMC), as shown by cryo-TEM (Figures 3C-II and 3C-III), whereas a pure network of branched worms was apparently observed after photo-PISA in 80.0 mM CHAPS solution. This was initially indicated on a macroscopic level by the formation a free-standing gel in the reaction vial after the polymerization process. The increase of both $D_h$ and PD noticed in this sample after purification is mainly attributed to further entanglement of the worm-like micelles during the centrifugation/resuspension process. Additional dry-state TEM imaging at [CHAPS] = 160.0 mM, clearly showed the development of small spherical micelles, confirming the results received from DLS analysis. As conversion $^1$H-NMR spectroscopy suggested that only 70% monomer consumption occurred after 2 h of reaction in this sample, an overnight photo-PISA reaction was repeated to ensure full monomer conversion. In this case, dry-state TEM imaging showed the formation of mostly small spherical micelles along with some short worms, derived from the integration of adjacent spheres (Figure S22). Similarly to the studied ionic surfactants, it is evident that the presence of high amounts of charged zwitterionic surfactant molecules promotes their ionic-like behavior and markedly affects the photo-PISA process, preventing the formation of higher-order structures. The incorporation of zwitterionic detergent molecules
into the bilayer of the assemblies combined with the introduction of charges in the hydrophilic corona of the nano-objects drives to the development of mixed polymer-surfactant formulations with higher interfacial curvature \((i.e.\) transitions to worm-like or spherical micelles\)). Above all, pure phases of ULVs, worms and spherical micelles were isolated by careful control of CHAPS concentration during aqueous photo-PISA of the same block copolymer. Surprisingly, in the case of the other studied zwitterionic phospholipid surfactant DPC, completely opposite behavior compared to high-CMC CHAPS and analogous to that of non-ionic and low-CMC detergents Triton™ X-100 and DDM was observed. In particular, minor size and PD variations were recorded for a wide range of DPC concentrations, in comparison to original PEG\(_{113}\)-b-PHPMA\(_{400}\) ULVs in DI water, suggesting that no dissociation to lower-order constructs occurred in this case, even at extreme detergent concentrations (Figure 3D-I). Hydrodynamic diameter of photo-PISA samples in DPC solutions ranged between 340 nm for low \([\text{DPC}]\) and 440 nm for higher \([\text{DPC}]\), while low PD values of 0.07 \(-\) 0.15 were also measured. It should also be noted that in the case of DPC, the purification process did not affect the \(D_h\) or PD values. Dry-state and cryo-TEM imaging at \([\text{DPC}] = 1.5 \text{ mM} (=\text{ CMC})\) revealed the successful development of pure spherical ULVs of uniform size (Figures 3D-II, 5B and S23). Based on cryo-TEM analysis, the average membrane thickness of vesicles formed at \([\text{DPC}] = \text{ CMC}\) was determined to be around 30 nm (Figure 3D-III). This indicates negligible interaction between DPC molecules and polymeric chains, following the same trend as low-CMC non-ionic surfactants. Additionally, the vesicular morphology and unilamellar character were retained upon increasing DPC concentration up to 20 times above its CMC value, showing the high tolerance of photo-PISA towards this particular surfactant (Figures 5B, S24 and S25). The marked differences observed between the two zwitterionic detergents are attributed to the higher weight percent of surfactant required in case of CHAPS \((\text{CMC}_{\text{CHAPS}} > \text{CMC}_{\text{DPC}})\), revealing the dual nature of such species that are possible to behave like non-ionic or ionic surfactants depending on the conditions. Finally, these
findings are of paramount importance as it was demonstrated that, besides neutral detergents, an ampholytic small molecule surfactant could also be used for applications of bio-relevant interest without drastically affecting the desired final morphologies prepared by aqueous PISA. The observed morphologies of all formulations developed by RAFT-mediated photo-PISA in aqueous surfactant solutions, as judged by dry-state and cryo-TEM, are summarized in Table S3.

A. High-CMC Zwitterionic Surfactant

[CHAPS]

Morphology Transition (Lower-Order Structures)

@ CMC

@ 10×CMC

@ 20×CMC

Low Curvature

High Curvature

B. Low-CMC Zwitterionic Surfactant

[DPC]

Morphology Retained (Higher-Order Structures)

@ CMC

@ 10×CMC

@ 20×CMC

Figure 5. (A) Representative dry-state TEM micrographs, stained with 1 wt% UA, reaction vial images and illustrations of the interfacial curvature of PEG113-b-PHPMA400 nano-objects developed by aqueous photo-PISA upon increasing concentration of high-CMC zwitterionic surfactant CHAPS. A vesicle-to-
worm morphology transition is observed at [CHAPS] = 10×CMC, while a subsequent worm-to-sphere transition is noticed at [CHAPS] = 20×CMC. (B) Representative dry-state TEM micrographs, stained with 1 wt% UA, of PEG₁₁₃-b-PHPMA₄₀₀ nano-objects developed by aqueous photo-PISA upon increasing concentration of low-CMC zwitterionic surfactant DPC. No morphology transitions were observed, hence ULVs of comparable sizes were received at concentrations ranging from [DPC] = CMC to 20×CMC.

Outer membrane protein F (OmpF) reconstitution into PEG₁₁₃-b-PHPMA₄₀₀ vesicles. Guided by the results on the tolerance of PISA to surfactants, a challenging functional membrane protein, which is not soluble in aqueous media in absence of surfactants, was selected for incorporation during the photo-PISA process. The channel-forming membrane protein OmpF trimer was extracted from Escherichia coli (See Supporting Information), purified and stabilized in an aqueous surfactant solution mixture of 0.39 mM DDM + 20 mM sodium phosphate (NaPhos) at pH = 6.0 (Figures S27 and S28). Initial photo-PISA reactions for the synthesis of PEG₁₁₃-b-PHPMA₄₀₀ block copolymers in 20mM NaPhos and 0.39 mM DDM + 20 mM NaPhos solutions (pH = 6.0) in absence of OmpF protein revealed that the controlled polymerization character (\(D_M \text{ ca.} = 1.3\), monomer conversion > 98%) and original vesicular morphology were retained in both cases, with negligible \(D_h\) and membrane thickness increases being observed (Figures S29 and S30). Importantly, 405 nm irradiation of DDM-stabilized OmpF for 2 h didn’t affect the secondary structure and hence functionality of the protein, as judged by circular dichroism (CD) measurements before and after light exposure (Figure S31). These findings suggest that by using this particular surfactant solution, OmpF could be directly reconstituted into the inherently permeable PHPMA membrane of vesicles by photo-PISA. Horseradish peroxidase (HRP) was chosen to be encapsulated into the lumen of both -OmpF and +OmpF-containing ULVs to provide a read-out of function of OmpF (permeability) by kinetic colorimetric assays, following a recently reported procedure by our group.³⁶
HRP catalyzes the oxidation reaction of the colorless substrate o-dianisidine to the colored (red-brown) dimer product, which can be detected by measuring the absorbance at $\lambda = 492$ nm over time (Figure 6A). The surfactant-stabilized OmpF protein was reconstituted into HRP-loaded ULVs by a one-pot photo-PISA reaction to introduce non-selective channels that would allow easier exchange of small molecules between the aqueous compartments of particles. From kinetic colorimetric analyses, a noticeable absorbance increase of $24 \pm 3\%$ was measured in case of purified +OmpF-containing ULVs compared to -OmpF ones, demonstrating the permeability enhancement of the former toward o-dianisidine and hydrogen peroxide and OmpF retention of function (Figure 6B-I). A similar permeability enhancement was also monitored upon ranging the particles’ concentration from 0.5 wt% to 0.1 wt% during kinetic colorimetric analyses. Dry-state TEM imaging confirmed the formation of OmpF-functionalized + HRP-loaded ULVs, while additional DLS analysis showed a negligible $D_h$ increase to $411 \pm 4$ nm, similar to that observed in DDM + NaPhos mixture without OmpF (Figures 6B-II, 6B-III and S32).
Figure 6. (A) HRP-catalyzed oxidation reaction of o-dianisidine to a red-brown colored dimer product, detected by colorimetric assay, taking place inside inherently permeable HRP-loaded PEG113-b-PHPMA400 vesicles and OmpF-functionalized + HRP-loaded PEG113-b-PHPMA400 vesicles. (B) Enzymatic activity of the purified empty (-HRP/-OmpF, blue line), HRP-loaded (+HRP/-OmpF, black line) and OmpF-functionalized + HRP-loaded (+HRP/+OmpF, red line) PEG113-b-PHPMA400 vesicles at 0.5 wt% (the inset shows the end-point microwells in each case) (I), intensity-weighted size distributions of purified OmpF-functionalized + HRP-loaded PEG113-b-PHPMA400 vesicles obtained by DLS, along
with the average $D_h$ and PD values (the error shows the standard deviation from 5 repeat measurements) (II) and representative dry-state TEM image, stained with 1 wt% UA (III).

CONCLUSIONS

In this study, an insight into the effect of different types of small molecule surfactants on aqueous photo-initiated PISA processes for the formation of polymer/surfactant complex nano-objects was explored. Investigation revealed the high tolerance of photo-PISA toward non-ionic surfactants with varying CMC values, as the originally targeted vesicular morphology was consistently retained in these cases. On the contrary, the high sensitivity of photo-PISA to the presence of ionic species was verified by the occurrence of morphological transitions towards lower-order structures upon increasing concentration of ionic surfactants. The introduction of charged molecules into the polymeric chains markedly affected the self-assembly process, leading to the development of formulations with larger interfacial curvatures. Moreover, the presence of zwitterionic surfactants of high or low CMC values was also studied. An interesting vesicle-to-worm-to-sphere morphology transition was observed upon increasing concentration of high-CMC zwitterionic surfactant, while in case of low-CMC detergent vesicular structures similar to those developed in non-ionic surfactant solutions were formed, at a wide range of concentrations. By using these results as a guide, a low-CMC non-ionic surfactant was selected for the stabilization/solublization of the hydrophobic channel-forming membrane protein OmpF, which was then able to be reconstituted into the membrane of the vesicles by a one-pot photo-PISA process. This highlights the robustness of photo-PISA for the in-situ insertion of delicate non-stable hydrophobic species to allow for the facile synthesis of biomimetic nanoreactors.
METHODS

Materials and Methods

Materials and characterization techniques used are included in Supporting Information. The syntheses of 4-cyano-4-[(ethylsulfanylthiocarbonyl)sulfanyl] pentanoic acid chain transfer agent (CEPA CTA) and poly(ethylene glycol)$_{113}$-CEPA macro-CTA (PEG$_{113}$-CEPA mCTA) by $N,N'$-dicyclohexylcarbodiimide (DCC) coupling between PEG$_{113}$ monomethyl ether and CEPA CTA were performed according to previously described processes with slight modification.$^{24,53}$ The synthetic procedures followed are given in detail in Supporting Information. All photo-PISA reactions were performed in a custom-built photo-reactor setup. This ensured the reaction mixture was only exposed to the light from the 400–410 nm LED source placed underneath the sample.

Synthesis of PEG$_{113}$-$b$-PHPMA$_{400}$ Diblock Copolymer Nano-Objects by Aqueous Photoinitiated Polymerization-Induced Self-Assembly (Photo-PISA) in Surfactant Solutions

A typical synthetic procedure to achieve PEG$_{113}$-$b$-PHPMA$_{400}$ diblock copolymer nano-objects at 10 wt% HPMA (or 11% solids content) by aqueous RAFT-mediated photo-PISA is described (Scheme S1)$^{24}$ PEG$_{113}$-CEPA mCTA (9.1 mg, 1.7 μmol, 1 eq) and HPMA (100 mg, 0.69 mmol, 400 eq) were dissolved in a freshly prepared aqueous surfactant solution of desired concentration (0.9 mL) in a sealed 20 mL scintillation vial bearing a magnetic stirrer bar. The resulting polymerization solution was degassed by purging with N$_2(g)$ for 15 min. The sealed vial was incubated at 37 °C with magnetic stirring under 405 nm light irradiation for 2 h to ensure full monomer conversion. After this period, the reaction mixture was exposed to air and allowed to cool to room temperature before conversion $^1$H-NMR and SEC analyses. The resulting solution of particles was then diluted ten-fold in DI water and purified by three
centrifugation/resuspension cycles in DI water at 14000 rpm for the removal of unreacted monomer and/or excess of non-incorporated surfactant molecules (Figure S1). $^1$H-NMR in methanol-$d_4$ and DMF SEC traces of the pure polymer were obtained after lyophilization of an aliquot of particles. TEM, DLS and zeta potential analyses were performed on samples after dilution to an appropriate analysis concentration.

**HRP Loading and OmpF Reconstitution into PEG$_{113}$-b-PHPMA$_{400}$ Vesicles by Aqueous Photo-PISA**

For the synthesis of permeable non-OmpF-containing HRP-loaded PEG$_{113}$-b-PHPMA$_{400}$ vesicles at 10 wt% HPMA by aqueous photo-PISA, a previously reported procedure was followed.$^{36}$ For the reconstitution of OmpF porin, PEG$_{113}$-CEPA mCTA (9.1 mg, 1.7 μmol, 1 eq) and HPMA (100 mg, 0.69 mmol, 400 eq) were first dissolved in DI water (0.53 mL) in a sealed 20 mL scintillation vial bearing a magnetic stirrer bar. Once homogeneous, 0.1 mL of a 200 U mL$^{-1}$ HRP solution in DI water and 0.27 mL of a 750 μg mL$^{-1}$ OmpF solution in 0.39 mM DDM + 20 mM NaPhos (pH = 6.0) were added. The resulting polymerization solution was degassed by purging with N$_2$(g) for 15 min. The sealed vial was incubated at 37 °C with magnetic stirring under 405 nm light irradiation for 2 h to ensure full monomer conversion. After this period, the reaction mixture was exposed to air and allowed to cool to room temperature before conversion $^1$H-NMR, kinetic colorimetric and microscopic analyses. The resulting solutions of non-OmpF and OmpF-containing particles were then diluted ten-fold in 100 mM PB (pH = 5.5) and purified by three centrifugation/resuspension cycles in 100 mM PB (pH = 5.5) at 14000 rpm for the removal of unreacted monomer, free HRP enzyme and/or non-incorporated OmpF molecules.

**ASSOCIATED CONTENT**
**Supporting Information.** The Supporting Information is available free of charge on the ACS Publications website at DOI:

Materials and characterization techniques, experimental details, additional SEC eluograms of PEG$_{113}$-b-PHPMA$_{400}$ diblock copolymers synthesized in DI water and various surfactant solutions, additional dry-state TEM and cryo-TEM images of nano-objects, OmpF reconstitution supplementary data (PDF)

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The manuscript was written through contributions of all authors. All authors have given approval to the final version of the manuscript.

**Notes**

The authors declare no competing financial interest.
ACKNOWLEDGMENTS

This work was supported by the ERC (638661, 294342 and 615142), EPSRC and University of Warwick. Dr. S. Bakker and Mr. R. Keogh (University of Warwick) are thanked for cryo-TEM assistance and Advanced BioImaging Research Technology Platform, BBSRC ALERT14 award BB/M01228X/1 is thanked for supporting cryo-TEM characterization. Dr. M. Hasan is thanked for CD assistance.

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